IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re Application of:	Art Unit: Not Yet Assigned
Pankaj B. Shah	Examiner: Not Yet Assigned
Appln. No.: not yet received	ATTY.'S DOCKET: ARL 03-19
Filed: even date herewith))
For: METHOD OF FABRICATING SUB-100 NANOMETER FIELD EMITTER TIPS COMPRISING GROUP III-NITRIDE SEMICONDEUCTORS	

INFORMATION DISCLOSURE STATEMENT [IDS]

Commissioner for Patents P.O. Box 1450 Alexandria, VA 22313-1450

Sir:

This Information Disclosure Statement is submitted in accordance with 37 CFR §\$1.97, 1.98, and it is requested that the information set forth in this statement and in the listed documents be considered during the pendency of the above-identified application, and any other application relying on the filing date of the above-identified application or cross-referencing it as a related application.

- [X] 1. This IDS should be considered, in accordance with 37 CFR §1.97, as it is filed within three months of the filing date of the above-identified national application or within three months of the entry into the national stage of the above-identified international application.
- [X] 2. In accordance with 37 CFR §1.98, this IDS includes a list (e.g., form PTO-1449) of all patents,

In re Appln. No.

publications, or other information submitted for consideration by the office, either incorporated into this IDS or as an attachment hereto. A copy of each document listed is attached.

[X] 3. No explanation of relevance is necessary for documents in the English language (see reply to Comments 67 and 68 in the preamble to the final rules; 1135 OG 13 at 20).

[X] 4. In accordance with 37 CFR §§1.97(g) and (h), the filing of this IDS should not be construed as a representation that a search has been made or that information cited is, or is considered to be, material to patentability as defined in §1.56 (b), or that any cited document listed or attached is (or constitutes) prior art. Unless otherwise indicated, the date of publication indicated for an item is taken from the face of the item and Applicant(s) reserves the right to prove that the date of publication is in fact different.

Respectfully submitted,

Date: 10/10/2003

Edward L. Stolarun

Attorney for Applicant(s)

Reg. No. 25,515 (703) 617-8051

Substitute for form 1449A/PTO

INFORMATION DISCLOSURE STATEMENT BY APPLICANT

(use as many sheets as necessary)

Sheet 1	of	2
---------	----	---

Complete if Known					
Application Number	Not yet received				
Filing Date	Even date herewith				
First Named Inventor	Pankaj B. SHAH				
Group Art Unit	Not yet assigned				
Examiner Name	Not yet assigned				
Attorney Docket Number	ARL 03-19	ナ			

	U.S. PATENT DOCUMENTS							
Examiner Initials*	Cite No.1	U.S. Patent Number	Document Kind Code ² (if known)	Name of Patentee or Applicant/Inventor	Date of Publication of Cited Document MM-DD-YYYY	Pages, Columns, Lines, Where Relevant Passages or Relevant Figures Appear		
	AA	5,536,193		Kumar	07-16-1996			
	AB	5,713,775		Geis, et al.	02-03-1998			
	AC	5,990,604		Geis, et al.	11-23-1999			
	AD	6,113,451		Hobart, et al.	09-05-2000			
	AE	6,218,771		Berishev, et al.	04-17-2001			
	AF	6,376,339		Linthicum, et al.	04-23-2002			
	AG	6,462,355		Linthicum, et al.	10-08-2002			
		·						
	Ì					-		
	Ì			-				

	FOREIGN PATENT DOCUMENTS							
			Foreign Patent Nu	mber	Name of Patentee or	Date of Publication		
Examiner Initials*	Cite No.1	Office ³	Number	Kind Code ⁵ (if known)	Applicant/Inventor of Cited Document	of Cited Document MM-DD-YYYY	Where Relevant Passages or Relevant Figures Appear	T⁵
								1 1
	<u> </u>							
							-	
								1

Examiner	Date	
Signature	Considered	

^{*} EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609. Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.

¹ Unique citation designation number. ² See attached Kinds of U.S. Patent Documents. ³ Enter Office that issued the document, by the two-letter code (WIPO Standard ST.3). ⁴For Japanese patent documents, the indication of the year of the reign of the Emperor must precede the serial number of the patent document. ⁵ Kind of document by the appropriate symbols as indicated on the document under WIPO Standard ST.16 if possible. ⁶ Applicant is to place a check mark here if English language Translation is attached.

Substitute for form 1449A/PTO

INFORMATION DISCLOSURE STATEMENT BY APPLICANT

Application Number Not yet received

Filing Date Even date herewith

First Named Inventor Pankaj B. SHAH

Group Art Unit Not yet assigned

Examiner Name Not yet assigned

Complete if Known

(use as many sheets as necessary)

		 		Addition it dillio	1101 701 00019110
Sheet	2	of	2	Attorney Docket Number	ARL 03-19

		OTHER PRIOR ART - NON PATENT LITERATURE DOCUMENTS	_
xaminer nitials*	Cite No. ¹	Include name of the author (in CAPITAL LETTERS), title of article (when appropriate), title of the item (book, magazine, journal, serial, symposium, catalog, etc.), date, page(s), volume-issue number(s), publisher, city and/or country where published	-
	АН	SOWERS, et al., "Thin films of aluminum nitride and aluminum gallium nitride for cold cathode applications," Appl. Phys. Lett., October 20, 1997, pp. 2289-2291, Vol. 71, No. 16.	
	AI	ZHELEVA, et al., "Dislocation density reduction via lateral epitaxy in selectively grown GaN structures," Appl. Phys. Lett., October 27, 1997, pp. 2472-2474, Vol. 71, No. 17.	
	AJ	UNDERWOOD, et al., "GaN field emitter array diode with integrated anode", J. Vac. Sci. Technol. B., March/April 1998, pp. 822-825, Vol. 16, No. 2.	
	AK	KOZAWA, et al., "Field emission study of gated GaN and Al _{0.1} Ga _{0.9} N/GaN pyramidal field emitter arrays," Appl. Phys. Lett., November 22, 1999, pp. 3330-3332, Vol. 75, No. 21.	
	AL	KUBALL, et al., "Focused Ion Beam Etching of Nanometer-Size GaN/AlGaN Device Structures and Their Optical Characterization by Micro-Photoluminescence/Raman Mapping," MRS Interent J. Nitride Semicond. Res., 2000, Vol. 5S1, Art. W12.3.	
	AM	GÜNTHER, et al., "Comparison of field emission from diamond and AIN coated Si Tips," EURO FE, September 25-29, 2000, Segovia-Spain.	
	AN	KASU, et al., "Spontaneous ridge-structure formation and large field emission of heavily Si-doped AlN," Appl. Phys. Lett., March 26, 2001, pp. 1835-1837, Vol. 78, No. 13.	
	AO	SUGINO, et al., "Field emission from GaN surfaces roughened by hydrogen plasma treatment," Appl. Phys. Lett., May 21, 2001, pp. 3229-3231, Vol. 78, No. 21.	
	AP	KASU, et al., "Field-emission characteristics and large current density of heavily Si-doped AIN and Al _x Ga _{1-x} N (0.38 ≤ x < 1)," Appl. Phys. Lett., November 26, 2001, pp. 3642-3644, Vol. 79, No. 22.	_
	AQ	TONDARE, et al., "Field emission from open ended aluminum nitride nanotubes," Appl. Phys. Lett., June 24, 2002, pp. 4813-4815, Vol. 80, No. 25.	
	AR	SHE, et al., "Silicon tip arrays with ultrathin amorphous diamond apexes," Appl. Phys. Lett., November 25, 2002, pp. 4257-4259, Vol. 81, No. 22.	

Examiner		Date	
Signature		Considered	
Market Committee of the	The second secon		

^{*} EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609. Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.

¹ Unique citation designation number. ² Applicant is to place a check mark here if English language Translation is attached.